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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/774,417	02/10/2004	Yoshiki Nishibayashi	50212-559	1031
75	590 02/17/2006		EXAM	INER
McDermott, Will & Emery			OLSEN, ALLAN W	
600 13th Street, Washington, D	, N.W. C 20005-3096		ART UNIT	PAPER NUMBER
Lemington, D	20001 2000		1763	

DATE MAILED: 02/17/2006

Please find below and/or attached an Office communication concerning this application or proceeding.

	Application No.	Applicant(s)				
	10/774,417	NISHIBAYASHI ET AL.				
Office Action Summary	Examiner	Art Unit	-			
	Allan Olsen	1763				
The MAILING DATE of this communication a Period for Reply	ppears on the cover sheet w	ith the correspondence address				
A SHORTENED STATUTORY PERIOD FOR REP THE MAILING DATE OF THIS COMMUNICATION - Extensions of time may be available under the provisions of 37 CFR after SIX (6) MONTHS from the mailing date of this communication. - If the period for reply specified above is less than thirty (30) days, a relif NO period for reply is specified above, the maximum statutory perions are reply within the set or extended period for reply will, by state Any reply received by the Office later than three months after the mail earned patent term adjustment. See 37 CFR 1.704(b).	I. 136(a). In no event, however, may a lepty within the statutory minimum of thir d will apply and will expire SIX (6) MONute, cause the application to become Al	reply be timely filed by (30) days will be considered timely. ITHS from the mailing date of this communication. BANDONED (35 U.S.C. § 133).				
Status						
1) Responsive to communication(s) filed on 12	December 2005.					
•						
3) Since this application is in condition for allow	Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under <i>Ex parte Quayle</i> , 1935 C.D. 11, 453 O.G. 213.					
Disposition of Claims						
4) ☐ Claim(s) 1,3 and 4 is/are pending in the appl 4a) Of the above claim(s) is/are withdr 5) ☐ Claim(s) is/are allowed. 6) ☐ Claim(s) 1,3 and 4 is/are rejected. 7) ☐ Claim(s) is/are objected to. 8) ☐ Claim(s) are subject to restriction and	awn from consideration.					
Application Papers						
9)☐ The specification is objected to by the Examir	ner.					
10)⊠ The drawing(s) filed on <u>04 August 2004</u> is/are	e: a)⊠ accepted or b)⊡ ob	jected to by the Examiner.				
Applicant may not request that any objection to the	e drawing(s) be held in abeyar	nce. See 37 CFR 1.85(a).				
Replacement drawing sheet(s) including the correct 11) The oath or declaration is objected to by the f		, , ,				
Priority under 35 U.S.C. § 119						
12) Acknowledgment is made of a claim for foreign a) All b) Some * c) None of: 1. Certified copies of the priority document of: 2. Certified copies of the priority document of: 3. Copies of the certified copies of the priority document of the priority document of the certified copies of the certified copies of the priority document of the certified copies of the c	nts have been received. nts have been received in A fority documents have been au (PCT Rule 17.2(a)).	pplication No. <u>09/995,854</u> . received in this National Stage				
Attachment(s)						
 Notice of References Cited (PTO-892) Notice of Draftsperson's Patent Drawing Review (PTO-948) Information Disclosure Statement(s) (PTO-1449 or PTO/SB/0 Paper No(s)/Mail Date 	Paper No(s	Summary (PTO-413) s)/Mail Date nformal Patent Application (PTO-152) ·				

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DETAILED ACTION

Continued Examination Under 37 CFR 1.114

A request for continued examination under 37 CFR 1.114, including the fee set forth in 37 CFR 1.17(e), was filed in this application after final rejection. Since this application is eligible for continued examination under 37 CFR 1.114, and the fee set forth in 37 CFR 1.17(e) has been timely paid, the finality of the previous Office action has been withdrawn pursuant to 37 CFR 1.114. Applicant's submission filed on December 12, 2005 has been entered.

Claim Rejections - 35 USC § 103

The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

Claims 1, 3 and 4 are rejected under 35 U.S.C. 103(a) as being unpatentable over the paper by Shiomi, "High-Rate Reactive Ion Etching of Diamond and Fabrication of Porous Diamond for Field-Emission Cathode", in New Diamond, Vol. 13, No 4. pp 28-29, in view of US Patent 6,261,726 issued to Brooks et al. and further in view of US Patent 6,013,191 issued to Nasser-Faili et al. and further in view of (hereinafter, Shiomi, Brooks and Nasser-Faili, respectively).

Shiomi teaches the reactive ion etching of a masked diamond surface. Shiomi teaches that the diamond is etched by a plasma of 100% O₂. Shiomi teaches that the angle of the sidewall can be controlled by adding CF₄ to the etchant. Shiomi teaches

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that vertical sidewalls can be obtained by adding a very small amount of CF₄. Shiomi teaches using a CF₄ concentration as low as 0.125%.

Shiomi does not teach supplying at least 0.45 W/cm² of power to the RIE process. Shiomi does not teach adding nitrogen to the etchant gas mixture.

Brooks teaches etching diamond with a mixture of O₂ and N₂ but Brooks does not teach using a fluorine containing etchant. See column 6, line 63.

Nasser-Faili teaches etching diamond with a plasma comprising O₂ and NF₃ while supplying 1.5 W/cm² of power to the RIE process. See column 3, lines 42-48 and column 6, lines 23-25.

It would have been obvious to one skilled in the art to etch diamond with plasma comprising O₂ and N₂ and a fluorine-containing compound because Shiomi and Brooks teach that a plasma consisting of 100% O2 and a plasma consisting of an O2 and N2 mixture are functionally equivalent with respect to etching diamond. It would be obvious to add the fluorine to the O₂/N₂ mixture of Brooks to gain the control over the etching profile as taught by Shiomi. The skilled artisan would have reasonable expectation of success in view of Nasser-Faili's teaching because Nasser-Faili demonstrates that etching diamond with a plasma comprising oxygen, fluorine and nitrogen with a low fluorine content, while supplying 1.5 W/cm² of power, results in the formation of vertical structures similar to those obtained by Shiomi.

Response to Arguments

Applicant's arguments have been considered but are moot in view of the new ground(s) of rejection.

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Conclusion

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Allan Olsen whose telephone number is 571-272-1441. The examiner can normally be reached on M-F 1-5.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Parviz Hassanzadeh can be reached on 571-272-1435. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Allan Olsen
Primary Examiner
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